

ABSTRACT OF DISCLOSURE

A manufacturing method of an air-pulse generating device is provided. The manufacturing method includes: providing a wafer including a first layer and a second layer; patterning the first layer of the wafer to form a slit with a zigzagging pattern; and removing a first part of the second layer. A portion of the first layer above the removed first part of the second layer forms a film structure. The slit with the zigzagging pattern separates the film structure into a first flap and a second flap. The slit with the zigzagging pattern zigzags in a back-and-forth manner among a first direction and extends toward a second direction. The air-pulse generating device produces a plurality of air pulses by actuating the film structure.

Fig. 20